

PELLICLE, PRODUCTION METHOD THEREOF, EXPOSURE METHOD

ABSTRACT

Provided are a pellicle for extreme ultraviolet light lithography, a
5 production method thereof, and an exposure method. A pellicle according to the
present invention includes a first frame having a pellicle film located thereon; a
second frame including a thick portion including a first surface carrying a surface
of the first frame opposite to a surface on which the pellicle film is located, and
also including a second surface connected with the first surface and carrying a
10 side surface of the first frame, the second frame enclosing the pellicle film and the
first frame; a through-hole provided in the thick portion of the second frame; and a
filter located on an outer side surface of the second frame and covering the
through-hole, the outer side surface crossing the surface of the first frame on
which the pellicle film is located.

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Fig. 2